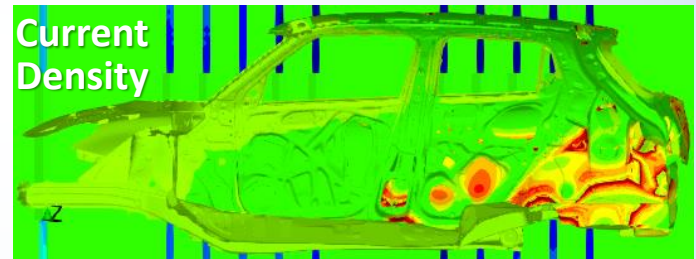
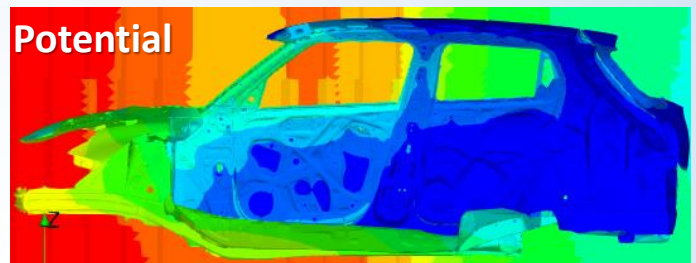
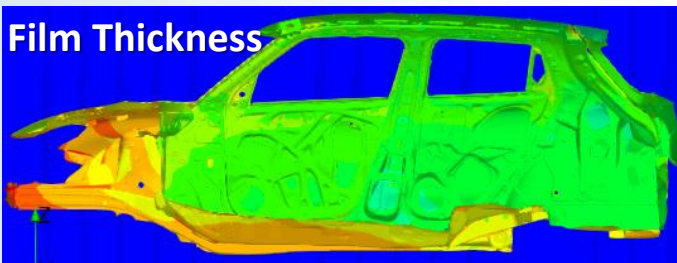
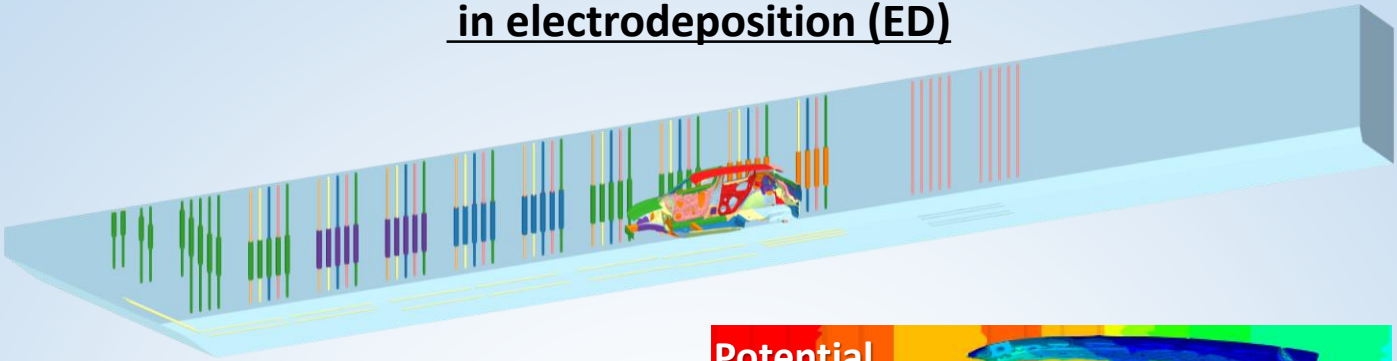


Electrodeposition Simulator EDES FEM

Numerical prediction of film thickness, potential, and current density
in electrodeposition (ED)



Applications

- Optimization of ED hole layout and ED conditions in vehicle design
- Pre-study of the effect of ED condition changes on film thickness
- Cause finding and quick improvement of insufficient deposition, etc.

Features

- Specialized for **actual line ED** in auto manufacturing
- Support for **moving boundary** analysis of multiple bodies
- Faithful reproduction of **deposition delay on inner plates**
- Good convergence under **highly nonlinear** cathodic BCs
- **High speed** w/ the MPI/OpenMP hybrid parallelization
- **High accuracy** w/ the next-gen FEM, “ES-FEM” (industry's first)

Notes:

Inquiry: <https://edes.fem.jp> edesfem@rccm.co.jp

- Paint property measurement tests are required, apart from the simulator.
- A tetrahedral meshing software (the “pre”) is required, in addition to the simulator.
- The free software “ParaView” (the “post”) is used for visualization.